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**CERTIFICATE OF MAILING**

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Tanya Parker  
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TECHNOLOGY CENTER 2800

Attorney Docket No.: NMTC-0756

**INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97**

**Inventor:** Youping Zhang  
**Title:** METHOD AND APPARATUS FOR CONTROLLING RIPPLING DURING OPTICAL PROXIMITY CORRECTION  
**Filing Date:** December 12, 2001  
**Serial Number:** 10/016,837  
**Group Art Unit:** 2825  
**Examiner:** To Be Assigned

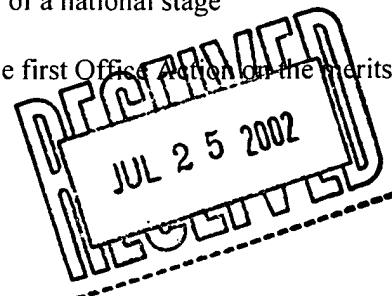
Listed below or on an attached Form PTO-1449 is information known to applicant(s) and submitted pursuant to 37 C.F.R. §1.56. A copy of each listed publication and U.S. and foreign patent, except for pending U.S. applications, is being submitted herewith, along with a concise explanation of information in a foreign language, if any, pursuant to 37 C.F.R. §1.97-1.98.

Applicants respectfully request that the listed information be considered by the Examiner and be made of record in the above-identified application. If form PTO-1449 is enclosed, the Examiner is requested to initial and return it in accordance with MPEP §609.

This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in §1.56.

This statement qualifies under 37 C.F.R. §1.97, subsection (b) because (check all that apply):

- (1) It is being filed within 3 months of the application filing date  
-- OR --
- (2) It is being filed within 3 months of entry of a national stage  
-- OR --
- (3) It is being filed before the mail date of the first Office Action on the merits.



— 37 C.F.R. §1.97(c). If this statement is being filed after the latest of: (1) three months beyond the filing date of a national application; (2) three months beyond the date of entry of the national stage as set forth in §1.491 in an international application; or (3) the mailing date of a first Office action on the merits, but before the mailing date of the earlier of a final office action under §1.113 or a notice of allowance under §1.311, then:

- a certification as specified in §1.97(e) is provided below; **or**
- a fee of \$240.00 as set forth in §1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement. Please note that a check in the amount of \$240.00 is enclosed in payment.

— 37 C.F.R. §1.97(d). If this statement is being filed after the mailing date of the earlier of a final office action under §1.113 or a notice of allowance under §1.311, but before payment of the issue fee, then:

- A. a certification as specified in §1.97(e) is completed below; **and**
- B. a petition under 37 C.F.R. §1.97(d) requesting consideration of this statement is submitted herewith; **and**
- C. a fee of \$130.00 as set forth in §1.17(i)(1) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.

— Statement under 37 C.F.R. §1.97(e) - I hereby certify that either: each item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign patent application not more than three months prior to the filing of the information disclosure statement; or no item of information contained in the information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign patent application, and, to the knowledge of the person signing the statement after making reasonable inquiry, no item of information contained in the information disclosure statement was known to any individual designated in section 1.56(c) more than three months prior to the filing of the information disclosure statement.

Signature: \_\_\_\_\_  
A. Richard Park (Reg. No. 41,241) Date

Respectfully submitted,

By:   
A. Richard Park  
Reg. No. 41,241

PARK, VAUGHAN & FLEMING LLP  
508 Second Street, Suite 201  
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(530) 759-1661

Date: July 11, 2002

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<b>INFORMATION DISCLOSURE CITATION</b> <b>PTO-1449</b> <b>JUL 15 2002</b> <b>JC56</b> <b>PATENT &amp; TRADEMARK OFFICE 89</b>		Atty. Docket No. NMTC-0756	Serial No. 10/016,837
		Applicant ZHANG, Youping	
		Filing Date 12/12/2001	Group 2825

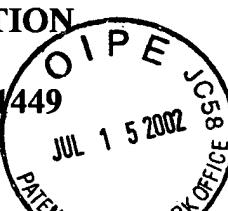
**FOREIGN PATENT DOCUMENTS**

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
	WO 00/67074 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
	GB 2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>

EXAMINER:

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<b>INFORMATION DISCLOSURE CITATION</b> 		Atty. Docket No. NMTC-0756	Serial No. 10/016,837
		Applicant ZHANG, Youping	TECHNOLOGY CENTER 2800 JUL 16 2002 RECEIVED
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**OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)**

EXAMINER'S INITIALS	CITATION
	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.
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Serial No.

10/016,837

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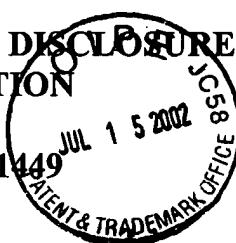
ZHANG, Youping

Filing Date

12/12/2001

INFORMATION DISCLOSURE  
CITATION

PTO-1449



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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
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	5,825,647	10/20/1998	Tsudaka	364	167.03	3/12/1996
	5,991,006	11/23/0199	Tsudaka	355	53	10/27/1997
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